20th Anniversary of KSDT

KISM 2022

Korean International Semiconductor Conference on Manufacturing Technology 2022

November 13-16, 2022 | Paradise Hotel Busan (Haeundae Beach), Busan, Korea

Session Title:	[TC3] Metal Etching
Session Date:	November 15 (Tue.), 2022
Session Time:	14:30-16:10
Session Room:	Room C (Grand Ballroom 2, 2F)
Session Chair:	Prof. Kenji Ishikawa (Nagoya Univ., Japan)

[TC3-1] [Invited] 14:30-15:00

80 nm-Line Etching of Copper Thin Films Using Ethylenediamine/Acetic Acid/Ar Gas Mixture

Sung Young Park, Seon Jae Kim, Seung Hyun Kim, Su Hyun Song, and Chee Won Chung (Inha Univ., Korea)

[TC3-2] [Invited] 15:00-15:30

Alternative Approach for Low Temperature Copper Dry Etching with Large Sized ECR Plasma Source

Jin Nyoung Jang, Jae Hoon Jung, Jong Hwa Lee, Kiro Jung (APS Research Corp., Korea), Donghoon Kim (Korea Univ., Korea), Sang-Gab Kim (Samsung Display Co., Ltd., Korea), Soo Ouk Jang (KFE, Korea), Chiwoo Kim (APS Research Corp., Korea), and MunPyo Hong (Korea Univ., Korea)

[TC3-3] 15:30-15:50

Atomic Layer Etching of Sn Using H_2/Cl_2 Radical

Yun Jong Jang, Doo San Kim, Hong Seong Gil, Hae In Kwon, Gyoung Chan Kim, and Geun Young Yeom (Sungkyunkwan Univ., Korea)

[TC3-4] 15:50-16:10

Clean Dry Etching of Ni Alloy Metal Thin Film for High Resolution Stretchable AMOLED

MupPyo Hong, Donghoon Kim, Sangheon Lee (Korea Univ., Korea), and Jin Nyoung Jang (APS Research Corp., Korea)